

Industry Air Filtration Solution with Compound Material

Multi-Fuction(toxic and harmful gas/solid pollutant) Compound Material Spec

Product Name	Weight (g)	Thickness (mm)	Gas pollutant cleaning efficiency (%)	Efficiency (%) 0.3μm	Pressure Drop (Pa) 32LPM	Air Permeability (L / m ² / s)
KL-CPS700-1	730±10%	2.6±0.4	≥90	F8H13	≤28	≥1200
KL-PSAM700-2	700±10%	2.8±0.3	≥90	F8 H13	≤43	≥900
KL-PSPB700-3	700±10%	2.25±0.4	≥90	F8 H13	≤39	≥1100

- 1) KI-CPS compound filter material was used to remove hydrogen sulfide, sulfur dioxide, organic matter and ozone in wet etching and metal deposition industry
- 2) KI-PSAM compound filter material was used to remove acid gas, amine, ammonia and N-methylpyrrolidone in lithography industry
- 3) KI-PSPB compound filter material was used to remove hydrogen arsenide, boron trifluoride, chlorine, hydrogen chloride, hydrogen fluoride, hydrogen sulfide and phosphine in the fields of etching, ion implantation and metal deposition
- 4) Able to clean the solid pollutant with efficiency grade F8-H13;
- 5) Weight and color customizable

1、Able to Compound with anti bacteria and virus material



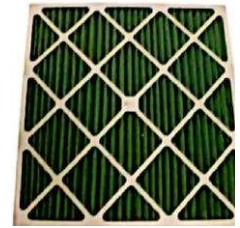
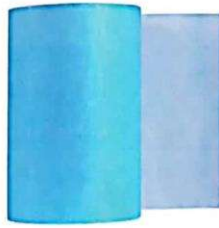
Toxic and harmful gas cleaning filter media (particle) spec

Product Name	Shape	Size	Stuff density (g / ml)	Strength (%)	Efficiency (%)
KL-FS2	cylindrical	Φ2	0.5 0.58	90	≥90
KL-FS2	cylindrical	Φ2	0.4 0.48	90	06<
KL-FS3	cylindrical	Φ2	0.4 0.48	90	>90
KL-TS1	globular	Φ2 globular	0.53 0.58	90	06<
KL-TS2	globular	Φ2 globular	0.47 0.52	90	06<
KL-TS3	globular	Φ2 globular	0.39 0.44	90	06

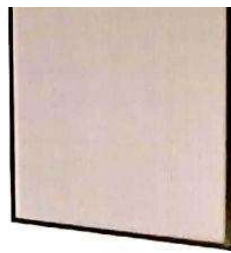
- 1) It can effectively remove the general gases such as Sox, NOx, O, VOCs, h, s, DMS, cos, total sulfur (TS), ci2 and other harmful gases;
- 2) It can effectively remove acid gases: HF, HCl, HBr, h, so;
- 3) It can effectively remove alkaline gases: NH3, NMP, CH, NH;
- 4) The filter material formula can be customized according to the type and concentration of the target polluted gas.

Industry Air Filtration Solution with Compound Material

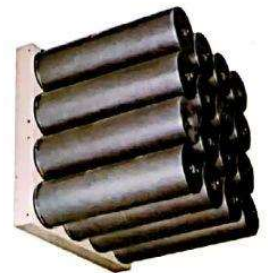
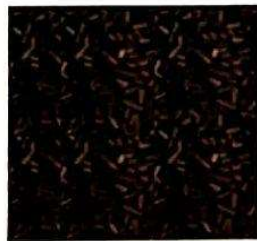
Primary Air Filter Media



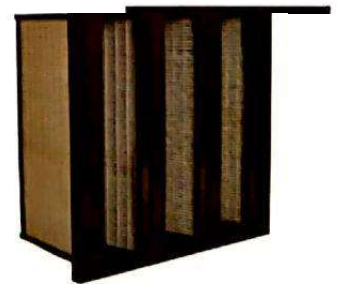
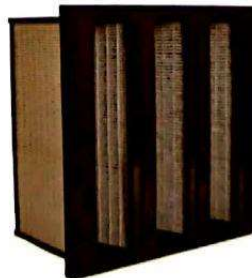
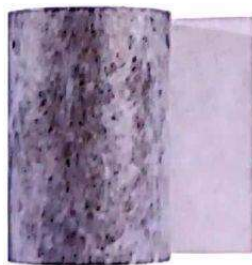
Medium and High Efficiency Filter Media



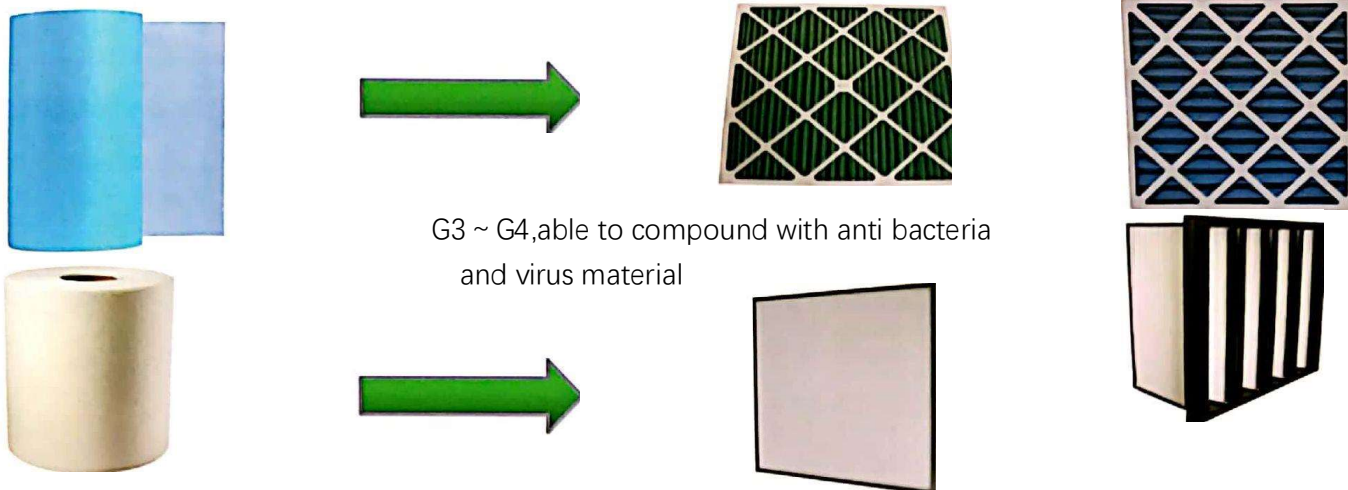
Gas Pollutant Filter Media



Gas/Solid Pollutant Filter Media



Industry Air Filtration Solution with Compound Material

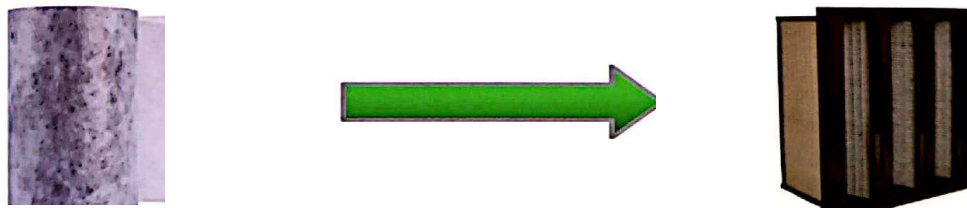


G3 ~ G4, able to compound with anti bacteria and virus material

Medium/High Efficiency Filter Media Spec

Product Name	Weight (g/m ²)	Thickness (mm)	Efficiency (%)	Pressure Drop (Pa)	Air Permeability (L / m ² / s)
KLR65L	85±10%	0.5±10%	≥65	≤7	≥1600
KLR85L	90±10%	0.5±10%	≥85(H10)	≤12	≥1000
KLR95L	95±10%	0.5±10%	≥95 (H11)	≤15	/
KLR99.5L	95±10%	0.6±10%	≥99.5(H12)	≤27	/
KLR99.97L	110±10%	0.6±10%	≥99.97(H13)	≤40	/

- 1、able to compound with anti bacteria and virus material; 2、color customizable



The central air conditioning ventilation system can eliminate low concentration of organic pollutants, sulfur dioxide and nitrogen dioxide, and has the functions of dust removal and pollutant gas removal;

For Air filtration in public places such as airports, hospitals (such as wards for patients with respiratory diseases) and office buildings the filter can effectively remove the peculiar smell in the air;

For Museums, archives, libraries and other places, it is able to remove sulfur oxides, nitrogen oxides and other polluting gases in the air, to protect the collection from damage;

For Central control rooms and data processing centers of chemical, petrochemical, iron and steel, banking, telecommunications and other enterprises the filters are used to protect precision instruments and data storage equipment from corrosive gases;

For Semiconductor and microelectronics manufacturing enterprises it should remove "airborne molecular contaminant" (AMC), improve product quality and protect personnel health;

In the laboratory animal room, the odor could be reduced, the quality of laboratory animals could be improved, and the atmospheric environment is protected.

Toxic and harmful gas cleaning filter media(compounded) spec

Product Name	Weight (g/m ²)	Thickness (mm)	Gas Pollutant Cleaning Efficiency (%)	Pressure Drop (Pa)	Air Permeability (L / m ² / s)	Remark
KL-SPB500	730±10%	2.6±0.4	90	≤10	≥700	Clean the H2S Pollutant for electronics and semiconductor industry
L-AFD005	700±10%	2.8±0.3	90	≤10	≥900	
KL-PSPB500	730±10%	2.25±0.4	90	≤10	≥700	
KLADC-G700	700±10%	2.5±0.4	85	≤10	≥700	